ORGANOMETALLICS

A (Borylmethyl)silane Bearing Three Hydrolyzable Groups on Silicon: Synthesis via Iridium-Catalyzed C(sp³)-H Borylation and Conversion to Functionalized Siloxanes

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Supporting Information

ABSTRACT: An iridium-catalyzed $C(sp^3)$ -H borylation of X_3 SiMe (X = hydrolyzable group) was established. A trialkoxy-(methyl)silane bearing sterically demanding neopentyloxy groups (X = neopentyloxy) underwent C-H borylation at the methyl group on silicon, giving (borylmethyl)tris(neopentyloxy)silane in 70% isolated yield. The choice of the hydrolyzable group X was the key to efficient and chemoselective C-H borylation; trialkoxy-



(methyl)silanes bearing sterically less demanding alkoxy groups (X = ethoxy, n-butyloxy, and isobutyloxy) suffered from C-H activation at the alkoxy groups, and trichloro(methyl)silane (X = Cl) failed to react. A trimethylsiloxy group could substitute the neopentyloxy groups of the borylated product by the reaction of trimethylsilanol in the presence of tetrabutylammonium fluoride.

onoorganosilanes bearing three hydrolyzable groups on Monoorganosilanes bearing the transformed and the silicon atoms (X_3 SiR: X = halogen or alkoxide; R =organic group) are important building blocks for the synthesis of branched polysiloxanes, including silsesquioxanes.¹ Another significant application of X₃SiR is their use as silane coupling agents, when the substituent R bears a functional group such as alkene and epoxide.² X₃SiR are synthesized by substitution of X₄Si with Grignard or organolithium reagents, but this method generally suffers from overreaction and therefore is not suitable for the selective introduction of a less hindered alkyl group.³ Chlorodephenylation of Ph₃SiR with HCl in the presence of AlCl₃ limits the substrate scope because of the harsh conditions.⁴ More general routes to X₃SiR are transitionmetal-catalyzed reactions of X₃SiH, i.e., hydrosilylation of unsaturated substrates⁵ and coupling with organohalides.⁶ Considering the recent increasing attention to the development of siloxane-based materials, new entries of efficient methods for the preparation of X₃SiR are still highly desirable. We focused on a synthetic route starting from Cl₃SiMe, which is a less utilized feedstock despite its second most production in the Rochow-Müller direct process.⁷ If the methyl group of Cl₃SiMe or its alkoxy derivatives can be converted to a functionalized organic group with retention of the hydrolyzable groups, it would be highly attractive for new access to X₃SiR.

We have pursued organosilicon compounds functionalized by a boryl group,⁸ which is expected to serve as a handle for the introduction of organic functional groups via C-C bond forming reactions or via capture of guest molecules on the boron atoms. We established an iridium-catalyzed C-H borylation of methylsilanes, which enabled conversion of the $C(sp^3){-}H$ bond of the methyl group on silicon. 9,10 The C–H borylation is applicable to methylchlorosilanes, including Cl₂SiMe₂ and ClSiMe₃.^{9a} However, the use of Cl₃SiMe in the C-H borylation protocol has met with difficulty. Herein we describe C-H borylation of methylsilanes bearing three hydrolyzable groups on the silicon atom (Scheme 1). We found a suitable hydrolyzable group X for efficient and chemoselective C-H borylation of the methyl group on silicon.

Scheme 1. Synthesis of Boryl-Functionalized Organosilicon Compounds Bearing Three Hydrolyzable Groups on the Silicon Atom

X	Ir-catalyzed C–H Borylation	X
X-SI-X Me	X = hydrolyzable group	x-SI-X B

We began our study by synthesizing (borylmethyl)trichlorosilane 1 by C-H borylation of Cl₃SiMe according to the method established previously for C–H borylation of Cl_2SiMe_2 and $ClSiMe_3$.^{9a} In the presence of $[Ir(OMe)(cod)]_2$ (5 mol %) and 3,4,7,8-tetramethylphenanthroline (Me₄phen, 10 mol %), Cl₃SiMe (4 equiv) was reacted with bis-(pinacolato)diboron (1 equiv) in cyclohexane at 80 °C (Scheme 2A). However, no reaction took place after 18 h. Under almost identical conditions, Cl₂SiMe₂ underwent C-H borylation to give **2** in high yield (Scheme 2B).^{9a} We separately observed that almost no reaction of Cl₂SiMe₂ took place in the presence of 20 mol % of Cl₃SiMe (Scheme 2B). These results

Received: April 19, 2016

Scheme 2. Cl_3SiMe in C–H Borylation: (A) C–H Borylation of Cl_3SiMe ; (B) C–H Borylation of Cl_2SiMe_2 in either the Absence or Presence of Cl_3SiMe

A	ClaSiMe	(pin)B–B(pin) (1 equiv) $[Ir(OMe)(cod)]_2$ (5 mol %) Me ₄ phen (10 mol %) // Cl ₂ Si ₂ B(pin)		
	(4	cyclohexane // 2	- (F····)	
	(4 equiv)	80 °C, 18 h	no reaction	
B (CLSiMer	(pin)B–B(pin) (1 equiv) [Ir(OMe)(cod)]₂ (2.5 or 5 mol %) Me₄phen (5 or 10 mol %)	MeSis B(nin)	
	(4 equiv)	Cl ₃ SiMe (0 or 20 mol %) cyclohexane 80 °C, 18 h	2	
		in the absence of CI_3SiMe^a in the presence of CI_3SiMe (20 mol %	85% 5) ^b trace	

 a [Ir(OMe)(cod)]₂ (2.5 mol %) and Me₄phen (5 mol %) were used. b [Ir(OMe)(cod)]₂ (5 mol %) and Me₄phen (10 mol %) were used.

indicate that Cl_3SiMe is a potential catalyst poison in the iridium-catalyzed C–H borylation.

We assumed that the highly Lewis acidic Cl₃SiMe might form a complex with Me₄phen, which caused deactivation of the iridium catalyst.¹¹ We turned our attention to the less Lewis acidic trialkoxy(methyl)silanes **3**, which could be prepared in a single step from Cl₃SiMe.¹² Triethoxy(methyl)silane (**3a**) reacted smoothly with bis(pinacolato)diboron in cyclooctane at 110 °C in the presence of the Ir-Me₄phen catalyst (10 mol %) (entry 1, Table 1). However, the reaction gave the

Table 1. Chemoselectivity in Iridium-Catalyzed C–H Borylation of Trialkoxy(methyl)silanes 3^{a}

(RO)₃SiMe 3a-d (4 equiv)		(pin)B–B [Ir(OMe)(Me₄phen cycloocta 110-135	(pin) (1 [cod)] ₂ (1 (10 mo ane °C, 18 h	equiv) 5 mol %) I %) > ((RO)₃Si B(p 4a-d	bin) + 5∶or€	ð or 7 or 8	
		(pin)B (pin)B	5 (R = 7 (R = is	SiMe(O = Et) O ^{SiMe} obutyl)	R) ₂ (pin) 9(OR) ₂ (p	BC 6 (R = <i>n</i> -E in)BC 8 (R = neope	SiMe(OR) ₂ Su) SiMe(OR) ₂ SiMe(OR) ₂	
	entry	R	L		temp (°C)	products	yield (%) ^b	(ratio) ^c
	1	Et		3a	110	4a + 5	98 (21	:79)
	2	<i>n</i> -Bu		3b	135	4b + 6	33 (67	:33)
	3	isobu	tyl	3c	135	4c + 7	57 (60	9:40)
	4	neope	entyl	3d	135	4d + 8	20 (>9	9:1)

^{*a*}[Ir(OMe)(cod)]₂ (0.025 mmol), Me₄phen (0.052 mmol), **3** (2.0 mmol, 4 equiv), and (pin)B–B(pin) (0.50 mmol) were reacted in cyclooctane (0.5 mL) at 110–135 °C for 18 h. ^{*b*}Combined yield of the structural isomers after purification. ^{*c*}Determined by ¹H NMR.

undesired 5, which was formed by borylation of the C–H bond at the terminus of the ethoxy group, as a major product with desired 4a (4a:5 = 21:79, entry 1). The formation of 5 is favorable because of the rather high reactivity of the C–H bond located β to the oxygen atom, as reported by Hartwig and coworkers.¹³ The C–H borylation of methylsilanes 3b,c bearing *n*-butyloxy and isobutyloxy groups, respectively,¹² proceeded at an elevated reaction temperature (135 °C) to give the borylated products with better chemoselectivity (4b:6 = 67:33 and 4c:7 = 60:40) (entries 2 and 3). Finally, we found that the sterically more demanding methyltris(neopentyloxy)silane (3d)¹² underwent C–H borylation selectively at the methyl group on silicon to afford 4d (4d:8 > 99:1), albeit in low yield (20%, entry 4). In this case, the C–H borylation at the methyl groups on the neopentyl group was retarded significantly by the steric hindrance.

We previously reported the effect of a catalytic amount of basic additives, e.g., *t*-BuOK, in acceleration of the iridium-catalyzed C–H borylation of aliphatic compounds.^{14,15} To improve the yield of 4d, the C–H borylation of 3d was performed in the presence of an additive (Table 2). We found

Table 2. Improvement of C–H Borylation for Synthesis of $4d^a$

1.	s si-	Me	(pin)B-B(pin) (1 equi [Ir(OMe)(cod)] ₂ (5 m Me ₄ phen (10 mol %)	iv) pl %)	∧ ∖ Si	\Si B(nin)	
3d (4 equiv)		IVIC	<i>t</i> -BuOK (0 or 2.5 mol neat 110 °C, 18 h	%)	۲۰۵٫3 4d	4d	
	entry	additi	ve (amt (mol %))	Ir:additiv	ve yiel	d (%) ^b	
	1	n	ione	-		24	
	2	t	-BuOK (1.25)	1:0.125	;	57	
	3	t	-BuOK (2.5)	1:0.25	75	(70) ^c	
	4	t	-BuOK (5.0)	1:0.5		36	
	5	t	-BuOK (7.5)	1:0.75		26	
	6	t	-BuOK (10)	1:1		18	
	7	t	-BuOK (15)	1:1.5		3	
	8	N	MeOK (2.5)	1:0.25		34	
	9	0	Cs_2CO_3 (2.5)	1:0.25		37	
	10	(CsF (2.5)	1:0.25		39	

^{*a*}[Ir(OMe)(cod)]₂ (0.025 mmol), Me₄phen (0.052 mmol), additive (0–15 mol %), **3d** (2.0 mmol, 4 equiv), and (pin)B–B(pin) (0.50 mmol) were reacted at 110 °C for 18 h. ^{*b*}Determined by ¹H NMR. ^cIsolated yield in multigram scale reaction. **4d** (3.0 g) was obtained.

that the reaction of 3d (4 equiv) with bis(pinacolato)diboron (1 equiv) took place efficiently at 110 °C in the presence of Ir-Me₄phen catalyst (10 mol %) and *t*-BuOK (2.5 mol %) without additional solvent, giving 4d in good yield (entry 3), while 4d was obtained only in 24% yield in the absence of *t*-BuOK under the same reaction conditions (entry 1). As observed in the previous study,¹⁴ the Ir-*t*-BuOK system is sensitive to the amount of *t*-BuOK. Rate acceleration was observed with an Ir:*t*-BuOK ratio of 1:0.5–0.125 (entries 2–4), whereas no acceleration was observed with the ratio of 1:1.5–1 (entries 6 and 7). Other additives such as MeOK, Cs₂CO₃, and CsF were not effective for the C–H borylation of 3d (entries 8–10). Finally, a multigram-scale reaction was carried out using the optimized ratio (Ir:*t*-BuOK = 1:0.25), by which 3.0 g of 4d (70% yield) could be synthesized (entry 3).

Although the neopentyloxy group is an uncommon hydrolyzable group in the formation of a Si–O–Si linkage, 4d could be converted to structurally defined oligosiloxanes by the reaction with an excess amount of trimethylsilanol in the presence of tetrabutylammonium fluoride (Scheme 3A).¹⁶ The reaction took place at 50 °C with retention of the boryl group to give siloxane 9 in 71% yield.

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Scheme 3. Synthesis of Functionalized Siloxanes: (A) Conversion of 4d to Siloxane 9 with Retention of the Boryl Group; (B) Conversion of 9 to Arylmethyl- and Hydroxymethyl-Substituted Siloxanes 10 and 11^a

A	Me₃SiOH (15 equiv) <i>n</i> -Bu₄NF (30 mol %) Me₂S	QSiMe₃ iiO−Si−OSiMe₂
40	THF 50 °C, 15 h	B(pin) 9 (71%)
В 9	Br–Ar (2 equiv) PdCl₂(dppf)∙CH₂Cl₂ (10 mol % Ba(OH)₂•8H₂O (6 equiv) H₂O (20 equiv) toluene	o) ► Me₃SiO-Si-OSiMe₃ Ar
	110-135 °C, 24-75 h	$\begin{array}{l} \textbf{10a} \; (Ar = 4 \text{-} \text{MeC}_6\text{H}_4, \; 110 \; ^\circ\text{C}, \; 75 \; \text{h}, \; 75\%) \\ \textbf{10b} \; (Ar = 3 \text{-} \text{MeC}_6\text{H}_4, \; 135 \; ^\circ\text{C}, \; 24 \; \text{h}, \; 70\%) \\ \textbf{10c} \; (Ar = 3 \text{-} \text{MeOC}_6\text{H}_4, \; 110 \; ^\circ\text{C}, \; 24 \; \text{h}, \; 83\%) \\ \textbf{10d} \; (Ar = 3 \text{-} \text{CF}_3\text{C}_6\text{H}_4, \; 135 \; ^\circ\text{C}, \; 24 \; \text{h}, \; 66\%) \end{array}$
	H ₂ O ₂ (20 equiv) NaHCO ₃ (5 equiv)	OSiMe₃ Me₃SiO−Si−OSiMe₃
	THF/H ₂ O (1:1) 50 °C, 11 h	OH 11 (80%)

^aIsolated yields are given.

The boryl group in 9 could be utilized for further functionalization and bond formation (Scheme 3B). Suzuki–Miyaura coupling of 9 with aryl bromides was carried out in toluene at 110–135 °C using DPPF/Pd catalyst with $Ba(OH)_2$ as a base to give 10a–d in good yields (Scheme 3B, top).^{9b,17,18} Treatment of 9 with H_2O_2 under basic conditions allowed the formation of hydroxymethyl-substituted siloxane 11 in 80% yield (Scheme 3B, bottom).¹⁹

In conclusion, we have established a synthetic method for boryl-functionalized methylsilanes bearing three hydrolyzable groups on silicon. Methyltris(neopentyloxy)silane was found to be a suitable substrate for chemoselective iridium-catalyzed C– H borylation at the methyl group on silicon. The neopentyloxy group of the borylated product was used as a hydrolyzable group in the formation of the Si–O–Si linkage with retention of the boryl group. Further utilization of this new T unit for the synthesis of functionalized polysiloxanes is being undertaken in this laboratory.

ASSOCIATED CONTENT

S Supporting Information

The Supporting Information is available free of charge on the ACS Publications website at DOI: 10.1021/acs.organo-met.6b00316.

Experimental details and characterization data of the products (PDF)

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Notes

The authors declare no competing financial interest.

ACKNOWLEDGMENTS

This work was supported by Grants-in-Aid for Scientific Research (B) (No. 26288048) and Scientific Research on

Innovative Areas "Molecular Activation Directed Toward Straightforward Synthesis (No. 25105728)" from the JSPS.

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(18) The use of 4d in Suzuki–Miyaura coupling was also examined. The reaction with 4-bromotoluene at 110 $^{\circ}$ C under the conditions shown in Scheme 3B gave the coupling product in 28% yield (see the Supporting Information).

(19) NaHCO₃ was a suitable base to obtain 11 in high yield. Use of NaOH instead of NaHCO₃ resulted in a low yield of 11, probably due to redistribution of the Si-O-Si linkage.